

<b>Notice of References Cited</b>	Application/Control No. 10/667,823	Applicant(s)/Patent Under Reexamination NOZAWA ET AL.	
	Examiner Rodney G. McDonald	Art Unit 1753	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,428,663	08-2002	Mostovoy et al.	204/298.12
	C	US-6,162,297	12-2000	Mintz et al.	118/715
	D	US-5,824,197	10-1998	Tanaka, Yoichiro	204/192.12
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	N	01-173718	07-1989	Japan	Fujikawa et al.	
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**NON-PATENT DOCUMENTS**

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	U	Kim et al. "Attenuated phase-shifting masks of chromium aluminum oxide", Applied Optics, Vol. 37, No. 19, pp.4254-4259, July 1, 1998.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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